

<b>Notice of References Cited</b>	Application/Control No. 09/842,370	Applicant(s)/Patent Under Reexamination WIESLER ET AL.	
	Examiner Chongshan Chen	Art Unit 2162	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-5,761,064	06-1998	La et al.	700/110
	C	US-			
	D	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Assessment of the performance of a reticle stocker with integrated database and the productivity gain obtained in a submicron ASIC waferfab, <a href="http://www.sea.rl.ac.uk/OldSEA/oldpubs/Retimatic/">http://www.sea.rl.ac.uk/OldSEA/oldpubs/Retimatic/</a>
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	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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